

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	35604	(plat\$3 electroplat\$3) and (electro\$1polish\$3 electro\$mechanical\$2 electro\$1planar\$5 electro\$1flatten\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/30 13:58
L2	2951	L1 and semiconductor adj (substrate wafer device)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/30 13:58
L3	2	L2 and ( mps sps dps (mercapto\$1propane dimercapto\$1propane) adj sulfonic dimethyl\$1dithiocarbamic) with accelerator	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/30 13:58
L4	837	( mps sps dps (mercapto\$1propane dimercapto\$1propane) adj sulfonic dimethyl\$1dithiocarbamic) with accelerator	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/30 13:59
L5	143	(plat\$3 electroplat\$3) and 4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/30 13:58
L6	30	5 and semiconductor adj (substrate wafer device)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/30 13:58
L7	30	6 and ( mps sps dps (mercapto\$1propane dimercapto\$1propane) adj sulfonic dimethyl\$1dithiocarbamic)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/30 13:59
S1	35604	(plat\$3 electroplat\$3) and (electro\$1polish\$3 electro\$mechanical\$2 electro\$1planar\$5 electro\$1flatten\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 15:24
S2	2951	S1 and semiconductor adj (substrate wafer device)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/30 13:46
S3	838	S2 and (plat\$3 electroplat\$3) same (electro\$1polish\$3 electro\$mechanical\$2 electro\$1planar\$5 electro\$1flatten\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 15:26

S4	381	S3 and (plat\$3 electroplat\$3) with (cu copper)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 15:25
S5	95	S4 not (@rlad>"20010405" @ad>"20010405")	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2005/09/29 15:26
S6	95	S5 and (plat\$3 electroplat\$3) same (electro\$1polish\$3 electro\$mechanical\$2 electro\$1planar\$5 electro\$1flatten\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 15:27
S7	95	S5 and (electro\$1polish\$3 electro\$mechanical\$2 electro\$1planar\$5 electro\$1flatten\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/29 15:27